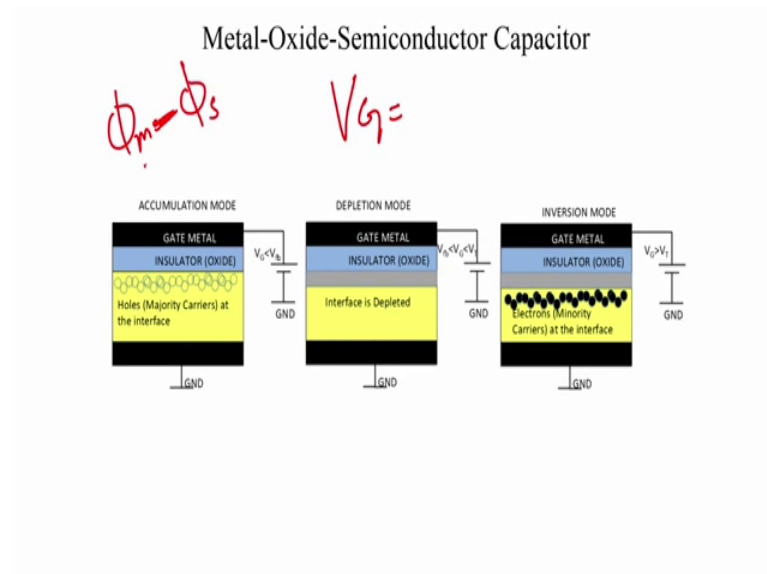


Semiconductor Devices and Circuits
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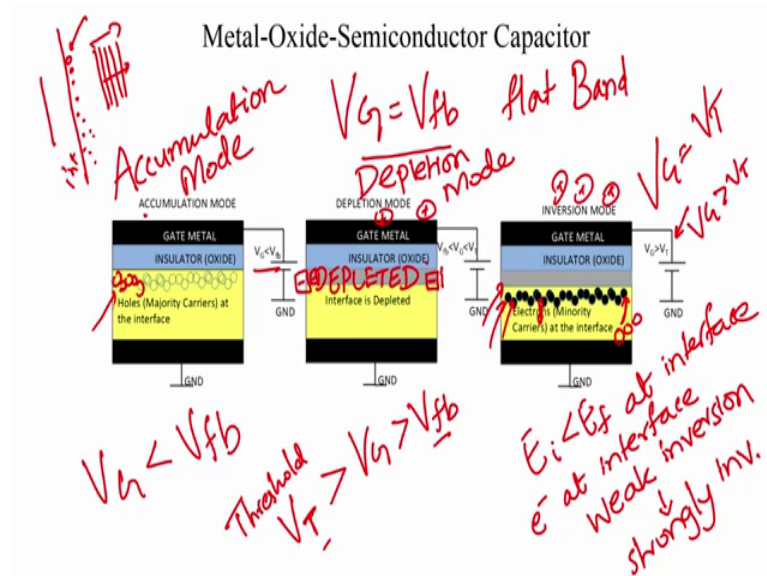
Lecture – 33
MOSCAP – Continued

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So, we defined something called the flat band voltage. So, at equilibrium the bands need not be flat it will be flat only when ϕ_m is equal to ϕ_s , but that need not be the case. And this $\phi_m - \phi_s$ is the driving force for any band bending at equilibrium, but now when we start applying a gate voltage we take the semiconductor we take the MOS capacitor out of equilibrium and when we make V_G equal to V_{fb} .

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We achieve flat band all the bands become flat. So, that is like a starting point for all our experiments all the bands of flat. And we need to create this kind of an offset voltage to make all the bands flat when we make V_G less than V_{fb} we bring the majority carriers at the interface. So, in this case; so here we are all talking about only a p type semiconductor ok. So, the same arguments hold for an n type semiconductor the only thing is you need to watch for the electrons being the majority carriers and holes being the minority carriers ok, but here we are talking about a p type semiconductor

So, when V_G is less than V_{fb} we bring holes to the interface ok. So, the hole start appearing at the interface. And this mode of operation is called as an accumulation mode of operation; so is again a technical term. So, when we say that the MOS capacitor is an accumulation mode operation it means that the gate voltage is such that the majority carriers in the semiconductor are at the interface.

Now, let us say we start making V_G greater than V_{fb} , but we are still less than V_T you know V_T is our threshold voltage. So, V_G is sitting somewhere between V_{fb} and V_T , but what happens in this case is that the gate metal now has positive charge ok. And therefore, it has to be balanced by the negative from the p type semiconductor and that is done by depleting the semiconductor. So, this is the depletion this region is all depleted. So, ideally speaking there are no free carriers in that region. So, the insulator

semiconductor interface is depleted. And in this case all the negatively charged acceptor ions are exposed and they are balancing all the positive charge on gate metal.

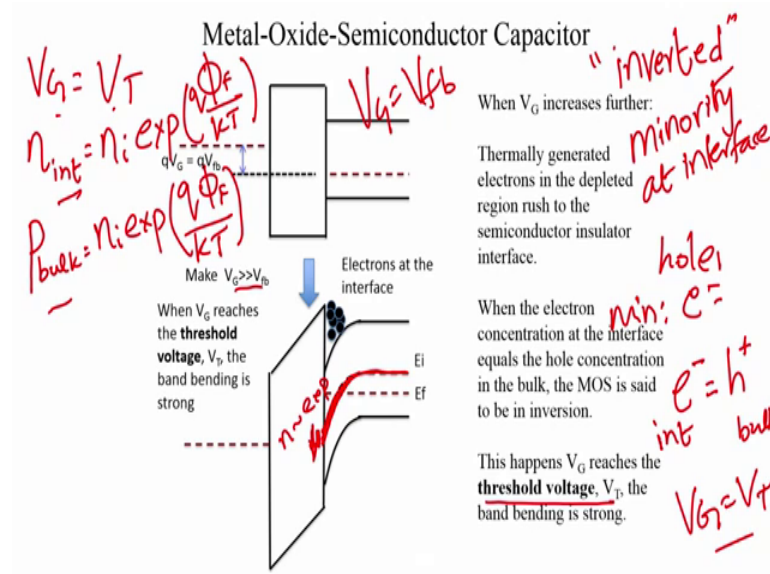
And this mode of operation is called as the depletion mode of operation depletion mode of operation. And then when you start increasing V_G further and further you first you will reach a point where the E_i starts going below E_f E_i starts going below E_f at interface and electrons will start appearing at the interface. So, when E_i is just started going below E_f it is something called as weak inversion weak inversion. And when E_i has gone well below E_f well below E_f and when the when the electrons at the interface when the electron concentration at the interface matches the hole concentration in the bulk. We say that the semiconductors the MOS capacitor strongly inverted strongly inverted strongly inverted.

And this happens at V_G equal to V_T . And when you make V_G greater than V_G all the excess positive charge in the gate is now mostly compensated by the electrons rushing at the interface and not so much by the depletion not so much by the depletion charge. The depletion width stops increasing. So, initially this is a story. So, initially you had flat band when you start making V_G greater than flat band first the first thing that happens is that depletion width.

So, let us say that is the interface the depletion width starts increasing ok. It uncovers more and more positive charge, but the moment electrons start appearing at the interface this increase in the depletion width more or less stops. Because a small increase in the gate voltage will exponentially increase the number of electrons at the interface. And therefore, you have a lot of electrons coming in there to balance any positive charge.

So, that is the story of everything that is going on in a MOS capacitor.

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So, go back and look at the band bending picture again just to make things clearer. So, the moment you hit inversion, so you see this bending. So, initially it was just bent like that. So, that was the depletion operation. And the moment it started bending like this you have an equal number of holes and electrons at the interface ok. And then, when you start bending it further down you have more electrons at the interface than the holes. And finally, reach a point when the electron concentration with the interface matches the hole concentration in the bulk and that is what the definition of our threshold voltages.

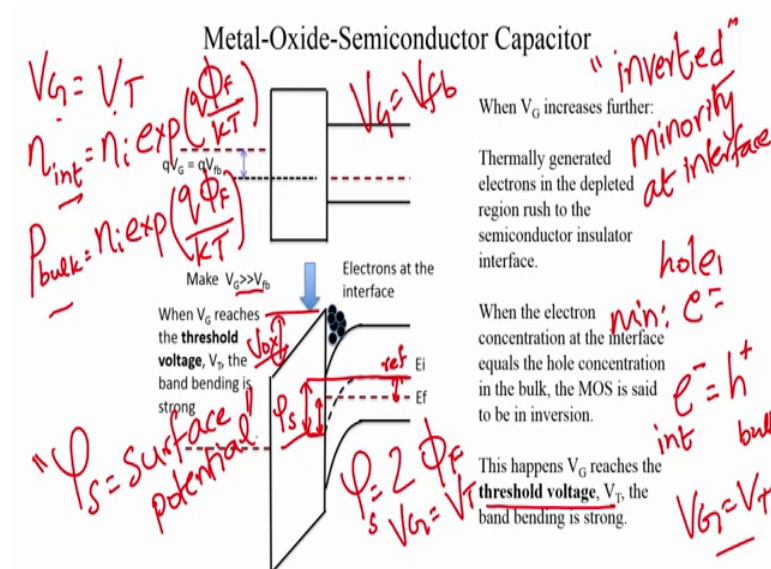
Now, if you still increase the gate voltage further, this band will not move too much more. It is not going to bend this much, because now the electrons have started appearing at the interface in large numbers. So, beyond at this point this band bending is not going to increase to much more. I mean you need to really make your gate voltage very very large for you to see any significant movement in the band bending that, and that is because for any small movement they export the electron population increases exponentially. And therefore, you have a lot of electrons coming in that easily balance all the charge and the gate.

So, you really need to make a significant amount you need to add a signature amount of positive charge in the gate in order for you to see any movement in the band bending. And therefore, after inversion or after threshold or after strong inversion you could say that the band bending is the bands are almost pinned ok. So, they are almost pinned at

this point they are not going to move too much. And another technical term which I should have probably mentioned is that is to define this potential.

So, let us say I create this voltage this built in potential as a reference ok.

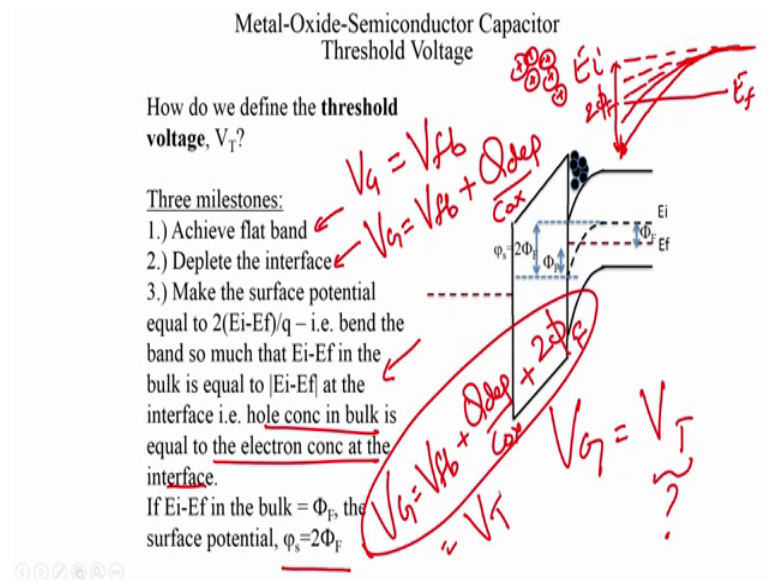
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So, let us say that is the reference potential. This potential which is the total amount of band bending in the semiconductor has got a special term, and it is called as the surface potential, ϕ_s is the surface potential ok. So, that is the complete band bending in the semiconductor.

So, at threshold voltage what is the surface potential? The surface potential is going to be $2\phi_f$, because it is going to be ϕ_f here and ϕ_f there ok. So, meant surface potential is equal to $2\phi_f$ your V_G is equal to your threshold voltage. So, this is a very useful term to remember, because we will keep using reference in this particular term. And since, we have defined the surface potential and if you define the voltage drop across the oxide, you can now the summation of the voltage drop across the oxide plus the surface potential has to be equal to V_G minus V_{fb} ok.

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So now how do we define threshold voltage? So, let us now start coming to a more quantitative definition of threshold voltage. Because it is such a useful in modeling parameter, but you must remember as I mentioned the semiconductors the electrons are not waiting for the threshold voltage to you know for the gate voltage across the threshold voltage before; V before they invert. I mean there is some weak inversion happening even before the surface potential reaches to ϕ_F ok. So, the moment the surface potential goes increases beyond ϕ_F you have electrons appearing quite rapidly at the interface. And these are all the thermally generated electrons here.

So now let us say how to define threshold voltage. There are 3 milestones right you need to cross these 3 milestones. So, how do I define V_G in a more quantitative manner? So, V_T looks good, but what is V_T exactly you know what does it depend on. So, there are 3 milestones. Firstly, let us make the bands flat. We do not know what the equilibrium gives you. So, let us first make the bands flat. So, V_G has to first cross. So, V_G must first equal the flat band voltage ok.

After that we keep increasing V_G you start depleting the interface. You know the bands you have E_f initially that was E_i it was all flat band ok. So, that is let me just draw this clearly. That was E_i it is flat band and now you start depleting the interface the E_i starts bending a little and you start having depletion. And then you keep bending a bit more you still have depletion. So, you then have to cross the second hurdle which is not only

have built put added a flat band voltage, but you start depleting the semiconductor and this total depletion charge by C_{ox} or the insulator capacitance is the effective voltage. That you need to add, and then you still start keep adding more and more positive charges still not enough. You have still not reach threshold you keep add adding more and more positive charge.

And now you will see E_i go below E_F . And now the electrons have started appearing, but we have still not reached threshold voltage. We reach threshold voltage only when the surface potential equals $2\phi_f$ ok. So, the third milestone is to make E_i bend the E_i minus E_f at the interface have the same magnitude as the E_i minus E_f in the bulk. Or in other words make the electron concentration of the interface match the hole concentration in the bulk. So, the hole concentration in the bulk and the electron concentration at the interface are the same. At this point the surface potential is $2\phi_f$ and your you have added enough charge to make V_G equal to V_{fb} plus the depletion charge plus $2\phi_f$. And when you have added enough charge to make all this happen then you can say that you have reached threshold voltage.

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Metal-Oxide-Semiconductor Capacitor
Threshold Voltage

$$V_t = V_{fb} + \frac{(-Q_{dep})}{C_{ox}} + 2\phi_f$$

Here Q_{dep} is the depletion charge per unit area

$$Q_{dep} = -qN_A x_d$$

C_{ox} is the insulator capacitance per unit area

$$C_{ox} = \epsilon_{ox} / t_{ox}$$

ϵ_{ox} = permittivity of the insulator

t_{ox} = thickness of the insulator

$V_{fb} = \Phi_{MS}$

We will fine tune the model for V_t when we discuss MOSFETs. This will involve, geometry dependence, trapped charges in the oxide etc.

And therefore, the threshold voltage has got these 3 components, it is got V_{fb} which is the flat band voltage it is got q depletion by C_{ox} and I put a minus sign here, because in this case it is all the acceptor ions. You will see because the q depletion has got a negative charge it is negatively charged acceptor ions. So, you first reach V_{fb} , it is the

flat band voltage then you deplete the semiconductor. And finally, you make the surface potential reach $2\phi_f$ and it is only when these 3 happen that you could say that that is enough charge in the gate that from this point on the semiconductor strongly inverted or the most capacitor strongly inverted and that voltage is the threshold voltage.

So, in some sense this is the definition of the threshold voltage. Now let us start getting into the details of these little terms here. So, what is V_{fb} , what is q depletion, what is the C_{ox} , what is ϕ_f , ok? So, what are these things? C_{ox} is the gate insulator capacitance per unit area ok. So, it is the gate capacity gate insulator capacitance per unit area. So, it is not the total capacitance.

So, since it is per unit area what does it depend on. So, let us say the insulator has got an permittivity of ϵ_{ox} , ϵ_{ox} for the oxide. And it is got a thickness of t_{ox} the total capacitance would be C is equal to $\epsilon_{ox} A$ by t_{ox} where A is the total area, but since we are looking at the per unit area capacitance C_{ox} is simply ϵ_{ox} by t_{ox} . So, that is your C_{ox} ok.

So, we understand that in term. What does q depletion? So, this is something you are already familiar with you have solved personas equation enough number of times that you know that in a p type semiconductor which is depleted. You have $q N_A$ as the charge minus $q N_A$ minus acceptor ions are all negatively charged minus $q N_A$ is the charge per unit volume in the semiconductor into the depletion width right. So, you have that is x_d and you have this minus $q N_A$ is the total charge per unit volume. And there is some area, but since we were looking at charge per unit area we do not really worry about that is a $q N_A$ into x_d ok.

If you had some area $q N_A$ into A into x_t would be the total charge present, because this charge per unit volume there is part of it which are you know is not visible on the display here.

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Metal-Oxide-Semiconductor Capacitor Threshold Voltage

$$V_T = V_{fb} + \frac{(-Q_{dep})}{C_{ox}} + 2\phi_F$$

$$C_{ox} = \frac{\epsilon_{ox}}{t_{ox}}$$

$$C_{ox} = \frac{\text{Gate Ins Gap}}{\text{area}}$$

Here Q_{dep} is the depletion charge per unit area

$Q_{dep} = -qN_A x_d$

C_{ox} is the insulator capacitance per unit area

$C_{ox} = \epsilon_{ox} / t_{ox}$

ϵ_{ox} = permittivity of the insulator

t_{ox} = thickness of the insulator

$V_{fb} = \phi_{MS}$

We will fine tune the model for V_T when we discuss MOSFETs. This will involve, geometry dependence, trapped charges in the oxide etc.

So, minus $q N_A a$ into x_d is the total charge present, because this is charge per unit volume it is the area and that is the depletion width. So, the charge per unit area is simply this stuff. So, that is your depletion charge. So, that is the amount of charge you need to put on the gate that is completely balanced by the depletion in the semiconductor ok.

So, you understand what this is you understand what this is what is V_{fb} ? V_{fb} is simply a ϕ_{ms} that is what is driving.

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Metal-Oxide-Semiconductor Capacitor Threshold Voltage

$$V_T = V_{fb} + \frac{(-Q_{dep})}{C_{ox}} + 2\phi_F$$

$$C_{ox} = \frac{\epsilon_{ox}}{t_{ox}}$$

$$C_{ox} = \frac{\text{Gate Ins Gap}}{\text{area}}$$

Here Q_{dep} is the depletion charge per unit area

$Q_{dep} = -qN_A x_d$

C_{ox} is the insulator capacitance per unit area

$C_{ox} = \epsilon_{ox} / t_{ox}$

ϵ_{ox} = permittivity of the insulator

t_{ox} = thickness of the insulator

$V_{fb} = \phi_{MS}$

We will fine tune the model for V_T when we discuss MOSFETs. This will involve, geometry dependence, trapped charges in the oxide etc.

All this it is a ϕ_m minus ϕ_s ϕ_s . Ok we call that as ϕ_{ms} . So, you understand what V_{fb} is, now V_{fb} can have more complications we will come to these things later on, but for now it is ϕ_m s , and what are these complications. These complications are that you could have charges trapped in the oxide you know you could have. So, that is that is one complication that we will look at. So, that will change the flat band voltage

But for now your V_{fp} is simplify ms that is the driving force for all the band bending at equilibrium. And what is ϕ_f ϕ_f is the surface potential at the interface when you have hit threshold voltage, but what is ϕ_f ϕ_f is the E_i minus E_f by q in the bulk right. And how do you know what is E_i minus E_f by q in the bulk. So, if you know the doping concentration, if you know N_A you can say N_A is approximately your p and p by n_i is equal to the exponential of ϕ_f by kT/q ϕ_f by kT . And therefore, ϕ_f is nothing, but kT/q into logarithm of your N_A by n_i . So, that is your that is your ϕ_f , and we have already done these kind of calculations before.

So, if you know the doping concentration you know the intrinsic carrier concentration you know what ϕ_f is ok. So, this is the threshold voltage. Now we are still not happy with this definition right. So, what is x_d ?

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Metal-Oxide-Semiconductor Capacitor
Threshold Voltage

$$\frac{d\psi}{dx} = -\frac{qN_A}{\epsilon_s} \Rightarrow \psi = -\frac{qN_A}{\epsilon_s}(x - x_d)$$

$$\frac{d\psi}{dx} = -\psi = +\frac{qN_A}{\epsilon_s}(x - x_d) \Rightarrow \psi = \frac{qN_A}{\epsilon_s}\left(\frac{x^2}{2} - x_d x\right)$$

If the bulk is at 0 potential (ref); the surface

$$\text{at } \psi_s = \frac{qN_A}{\epsilon_s} \frac{x_d^2}{2} \Rightarrow x_d = \left(\frac{2\epsilon_s \psi_s}{qN_A}\right)^{1/2}$$

$$Q_{dep} = -qN_A x_d = -(2\epsilon_s \psi_s qN_A)^{1/2}$$

$$V_T = \phi_{MS} + \frac{(4q\epsilon_s \phi_F N_A)^{1/2}}{qC_{ox}} + 2\phi_F$$

$Q_{dep} = qN_A x_d$

$2\phi_F = \phi_s$

We have not defined x_t . And how do you define x_t ? You solve Poisson's equation. So, we have done this many times you just write you assume full depletion you make the assumption of full depletion that is there are no free carriers. Therefore, Poisson's

equation is simply this term here and therefore, your x_d your potential turns out to be this term. So, I will not go through these details or I think all of you are, now at this point familiar with all this that is the potential and if you say that the bulk is at 0 potential the interface. So, the bulk is that 0 potential the interface will have a potential of this term here and that is the surface potential.

So, that is the surface potential at the interface. And what is x_d : x_d can be written in terms of the surface potential as this. So, what is the surface potential again? It is you are imagining the intrinsic Fermi level bending this way. So, if you keep your bulk as the reference let us say that is reference or ground. It is this difference. So, that is your surface potential. So, the surface potential equals $2\phi_f$. Then we have reached threshold voltage. It could be less than to 5, but when you reach $2\phi_f$ it is threshold voltage and when surface potential is greater than $2\phi_f$ you are above threshold ok.

But as I mentioned that after inversion the surface potential is more or less pinned it is not bands are not going to bend too much more. I think the surface potential is more or less pinned and therefore, you can now say the threshold voltage is V_{fb} which is now written out as ϕ_{ms} . This is q depletion by C_{ox} , because now we have taken into account x_d ok. So, you multiply. So, q depletion now becomes q_i have taken care of the negative signs we have removed all that; so q_{NA} into x_d ok. Let us q depletion is the charge in depletion charge per unit area q_{NA} into x_d and for x_d you substitute this term here and you will end up with this being the value for q depletion. And that is C_{ox} we already know what C_{ox} is it is the capacitance the oxide capacitance the insulated capacitance per unit area plus ϕ_s and at threshold ϕ_s is $2\phi_f$ ok.

So, that is the threshold voltage. So, if you know the doping concentration you basically know ϕ_f . And so, here again here the surface potential term inside has been.

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Metal-Oxide-Semiconductor Capacitor
Threshold Voltage

$Q_{dep} = q N_A x_d$

$$\frac{d\psi}{dx} = -\frac{q N_A}{\epsilon_s} \Rightarrow \psi = -\frac{q N_A}{\epsilon_s} (x - x_d)$$

$$\frac{d\psi}{dx} = -\psi = +\frac{q N_A}{\epsilon_s} (x - x_d) \Rightarrow \psi = \frac{q N_A}{\epsilon_s} \left(\frac{x^2}{2} - x_d x \right)$$

If the bulk is at 0 potential (ref); the surface

$$\psi_s = \frac{q N_A}{\epsilon_s} \frac{x_d^2}{2} \Rightarrow x_d = \left(\frac{2 \epsilon_s \psi_s}{q N_A} \right)^{1/2}$$

$$Q_{dep} = -q N_A x_d = -\left(2 \epsilon_s \psi_s q N_A \right)^{1/2}$$

Threshold at ψ_s

$$V_T = \Phi_{MS} + \frac{(4 q \epsilon_s \psi_s N_A)^{1/2}}{C_{ox}} + 2 \phi_F$$

$2\phi_F = \psi_s$

Two ψ_s have been substituted for the surface potential term. So, that is why you have ψ_s there if you know the doping concentration, you know ψ_s if you know this you know if you know ϵ_s and N_A that is the permittivity of the semiconductor and that is the work function difference between the metal and the semiconductor. So, this work function difference divided by C_{ox} . So, this is the potential term, it is a potential. And you end up with the threshold voltage which is a very useful modeling parameter.

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Metal-Oxide-Semiconductor Capacitor
Key relations

$$(V_g - V_{fb}) = V_{ox} + \phi_s$$

$$C_{ox} V_{ox} = -(Q_{dep} + Q_{inv}) \Rightarrow V_{ox} = -\frac{(Q_{dep} + Q_{inv})}{C_{ox}}$$

Here, Q_{inv} , is the inversion charge per unit area (made of electrons)

$$\Rightarrow V_g - V_{fb} = -\frac{(Q_{dep} + Q_{inv})}{C_{ox}} + \phi_s$$

$$\Rightarrow V_g - V_T = -Q_{inv} / C_{ox} = qN / C_{ox} \Rightarrow qN = C_{ox} (V_g - V_T)$$

Here, N , is the number of electrons per unit area.

Also,

$$\epsilon_{ox} \xi_{ox} = \epsilon_s \xi_s$$

$$\xi_{ox} = \text{Field in the oxide}$$

$$\xi_s = \text{Field in the semiconductor}$$

So, here are some very important or useful relations, we will sort of summarize all this by these equations here; so V_G minus V_{fb} . So, let us say. So, let us do pardon this usage of s ok. So, that is just a force of habit. So, you can say s is the reference potential here. So, once we learn MOSFETs you will understand what the V_G is, but just replace all s with just V_G ok. So, you have V_G minus V_{fb} is the driving force.

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Metal-Oxide-Semiconductor Capacitor
Key relations

$$\boxed{V_{gs} - V_{fb} = V_{ox} + \phi_s}$$

$$C_{ox} V_{ox} = -(Q_{dep} + Q_{inv}) \Rightarrow V_{ox} = -\frac{(Q_{dep} + Q_{inv})}{C_{ox}}$$

Here, Q_{inv} , is the inversion charge per unit area (made of electrons)

$$\Rightarrow V_{gs} - V_{fb} = -\frac{(Q_{dep} + Q_{inv})}{C_{ox}} + \phi_s$$

$$\Rightarrow V_{gs} - V_T = -Q_{inv} / C_{ox} = qN / C_{ox} \Rightarrow qN = C_{ox} (V_{gs} - V_T)$$

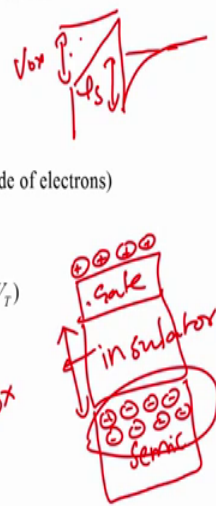
Here, N , is the number of electrons per unit area.

Also,

$$\epsilon_{ox} \xi_{ox} = \epsilon_s \xi_s$$

ξ_{ox} = Field in the oxide

ξ_s = Field in the semiconductor



That is the x . So, we have V_G is equal to V_{fb} you have flat band there are no voltage drops anywhere, but when V_G is different from V_{fb} you start having a you have start having electric fields in the oxide and in the semiconductor. And therefore, you have some voltage drop across the oxide and the semiconductor.

So, the first key relation is that V_G minus V_{fb} that voltage has to be split between the oxide and the semiconductor. And in the semiconductor it will be it will appear as the surface potential. So, let us say that is the drop across the oxide the remainder of it will be seen as the built in on the surface potential in the semiconductor. So, V_{ox} plus ϕ_s is equal to your V_G minus V_{fb} , but what is V_{ox} ? Think of the semiconductor like this ok. So, you have you have the gate metal you have the insulator and you remember this is a MOS capacitor right. And you have the semiconductor and all the charge here is being compensated by some all the negative charges in the semiconductor by depletion charge or by electrons. So, this is your most capacitor in action right.

So, what is this? If you think of it as a fuse your old, I mean your conventional capacitor notations. That is C_{ox} that is the oxide capacitance per unit area, into V_{ox} is the voltage across this capacitor right as the voltage across the insulator right. That is the voltage difference voltage drop across the insulator that is V_{ox} . So, C_{ox} into V_{ox} has to be the charge stored on the gate ok. And the charge stored on the gate is the charge in the semiconductor ok. And what are the charge in the semiconductor, that it is a summation of the depletion charge and the inversion charge ok.

So, C_{ox} is all per unit area here. So therefore, your C_{ox} into V_{ox} is equal to the depletion charge plus the inversion charge. And I put a negative sign because all this is a negative charge for this example. And therefore, your V_{ox} is simply the depletion charge per unit area plus the inversion charge by inversion charge you mean that you mean the electrons that have appeared at the interface the inversion the minority carriers ok.

So, you have the depletion charge, you have the inversion charge divided by C_{ox} is your V_{ox} . And now, we will substitute for this V_{ox} here and what do you get you get V_G minus V_{fb} is V_{ox} plus ϕ_s , but you have already defined the threshold voltage isn't it. So, the threshold voltage is V_{fb} it has the q depletion by C_{ox} and it has got the ϕ_s term in it. So, if you replace these 3 terms with the one term which is the threshold voltage, what we are essentially saying from all these equations is that V_G minus V_T that is the excess gate voltage above the threshold voltage ok.

(Refer Slide Time: 25:22)

Metal-Oxide-Semiconductor Capacitor
Key relations

$V_{gs} - V_{fb} = V_{ox} + \phi_s$

$C_{ox} V_{ox} = -(Q_{dep} + Q_{inv}) \Rightarrow V_{ox} = -\frac{(Q_{dep} + Q_{inv})}{C_{ox}}$

Here, Q_{inv} , is the inversion charge per unit area (made of electrons)

$\Rightarrow V_{gs} - V_{fb} = -\frac{(Q_{dep} + Q_{inv})}{C_{ox}} + \phi_s$

$\Rightarrow V_{gs} - V_T = -Q_{inv} / C_{ox} = qN / C_{ox} \Rightarrow qN = C_{ox} (V_{gs} - V_T)$

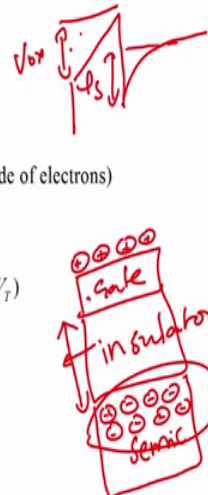
Here, N_s is the number of electrons per unit area.

Also,

$\epsilon_{ox} \mathcal{E}_{ox} = \epsilon_s \mathcal{E}_s$

$\mathcal{E}_{ox}$ = Field in the oxide

$\mathcal{E}_s$ = Field in the semiconductor



overarchive

And that is something called as the overdrive voltage it is helpful to know this term in case you hear this in the context of MOSFETs what they are saying is it is V_G minus V_T ok.

So, again let us just replace all this as V_G . So, V_G minus V_T , because I have now gotten taken care of these 3 terms is simply your q inversion by C_{ox} . So, what you are saying is that.

(Refer Slide Time: 25:49)

Metal-Oxide-Semiconductor Capacitor
Key relations

$V_{gs} - V_{fb} = V_{ox} + \phi_s$



$$C_{ox} V_{ox} = -(Q_{dep} + Q_{inv}) \Rightarrow V_{ox} = -\frac{(Q_{dep} + Q_{inv})}{C_{ox}}$$

Here, Q_{inv} , is the inversion charge per unit area (made of electrons)

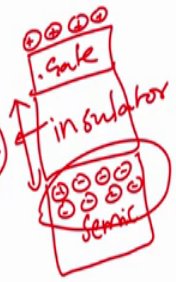
$$\Rightarrow V_{gs} - V_{fb} = -\frac{(Q_{dep} + Q_{inv})}{C_{ox}} + \phi_s$$

$$\Rightarrow V_{gs} - V_T = -\frac{Q_{inv}}{C_{ox}} = qN / C_{ox} \Rightarrow qN = C_{ox} (V_{gs} - V_T)$$

Here, N , is the number of electrons per unit area.

$-qN$
Also,
 $\epsilon_{ox} \xi_{ox} = \epsilon_s \xi_s$
 ξ_{ox} = Field in the oxide
 ξ_s = Field in the semiconductor

$Q_{inv} = C_{ox} (V_{gs} - V_T)$



If you want to know how many electrons are there the semiconductor insulator interface, you want to calculate you essentially want to calculate q inversion. What you need to do is simply say that q inversion is equal to C_{ox} into V_G minus V_T ok, the magnitude of q . So, V_G minus V_T is the voltage access voltage above the threshold voltage because still threshold voltage you did not have inversion charge.

So, you do not have a lot of it, but above the threshold voltage you start having inversion. And therefore, the excess voltage everything that go all the V_G what this is saying is that all the V_G above the threshold voltage is creating electrons at the interface. And you can further write q inversion as q into n ok. Where n is the number of electrons per unit area and therefore, here you have the number of electrons if you want to know how many electrons are there per unit area.

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Metal-Oxide-Semiconductor Capacitor
Key relations

$$V_g - V_{fb} = V_{ox} + \phi_s$$

$$C_{ox} V_{ox} = -(Q_{dep} + Q_{inv}) \Rightarrow V_{ox} = -\frac{(Q_{dep} + Q_{inv})}{C_{ox}}$$

Here, Q_{inv} , is the inversion charge per unit area (made of electrons)

$$\Rightarrow V_g - V_{fb} = -\frac{(Q_{dep} + Q_{inv})}{C_{ox}} + \phi_s$$

$$\Rightarrow V_g - V_T = -Q_{inv} / C_{ox} = qN / C_{ox} \Rightarrow (qN = C_{ox}(V_g - V_T))$$

Here, N , is the number of electrons per unit area.

Also,

$$\epsilon_{ox} \xi_{ox} = \epsilon_s \xi_s$$

ξ_{ox} = Field in the oxide
 ξ_s = Field in the semiconductor

At the interface that is the answer ok. So, that those are some useful relations which will help you imagine the situation a little better.

So, that you are not surprised when we just start writing these equations. So, it all comes from this basic understanding or this description of your device so far. The other relation now how do you find out what ϕ_s because you have one equation, but I still cannot calculate ϕ_s I know what V_g because I am applying V_g . We can find out what V_{fb} is by looking up the metal and semiconductor work functions, but we still not still do not know what ϕ_s ok. Because we do not know what Q_{dep} 's here, we Q_{dep} 's V_{ox} all this term, but we cannot calculate it without calculating ϕ_s because your Q_{dep} is also dependent on ϕ_s ok.

So, you see it is a quadratic relation your Q_{dep} does depend on ϕ_s and you also have a ϕ_s there. So, we need another equation. Now the other equation is equating the displacements at the insulator semiconductor interface. So, what this equation says is the $\epsilon_{ox} \epsilon_{ox}$, electric field in the oxide this product at this interface must be must be continuous, which means it must match ϵ_s into the electric field in the semiconductor.

And you can calculate the electric field in the semiconductor by solving Poisson's equation. And that calculation will have an x or a ϕ_s dependence on it. And by using this relation you can estimate what ϕ_s is and what is ϵ_{ox} it is simply going to

be your V_G minus ϕ_s by t_{ox} in a very crude sense if there are no trapped charges in the oxide that is it. So therefore, you have 2 relations with ϕ_s in it and you solve for ϕ_s . And these are not easy equations to solve ok.

So, with that we complete the basic understanding of the MOS capacitor, you know how the MOS capacitor works the operation of the MOS capacitor. And from this point on we will start looking at some electrical properties, particularly what is the capacitance of the MOS capacitor. We will start quantifying the capacitance. And this piece of information this knowledge is quite useful when we start talking about MOSFETs.